

Ben has been actively involved in the Metrology field for 8 years focusing upon reverse engineering practices using structured light scanning and photogrammetry. His past research as faculty at Clemson University has included developing pathways for entry into the metrology field and measuring the associated learning outcomes in order to become a professional metrologist. His research interests include: SDK programming for worker assistance, self-build structured light scanning methods and texture mapped heritage documentation. He has spoken at a number of professional conferences including invited lectures at The Smithsonian Institute and Texas A&M.